ABSTRACT

A sulfonate compound having formula (1) is novel

wherein R¹ to R³ are H, F or C₁-₂₀ alkyl or fluoroalkyl, at
least one of R¹ to R³ contains F. A polymer comprising units
derived from the sulfonate compound is used as a base resin
to formulate a resist composition which is sensitive to
high-energy radiation, maintains high transparency at a

wavelength of up to 200 nm, and has improved alkali
dissolution contrast and plasma etching resistance.

$$0 = S = 0$$

$$0$$

$$R^{1} \xrightarrow{Q} R^{2}$$

$$R^{3}$$

$$(1)$$